

525 U.S. PTO
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LIST OF PUBLICATIONS CITED BY APPLICANT	<u>Attorney Docket No.</u> SEL 173	<u>Serial No.</u> Not Assigned
	<u>Applicant</u> Hisashi OHTANI et al	09/535,836
	<u>Filing Date</u> Herewith 03/28/00	<u>Group</u> Z81

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*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE
Vn	5,594,569	01/14/97	Konuma et al	349	122	07/20/94
Vn	5,643,826	07/01/97	Ohtani et al	437	88	10/25/94
Vn	5,648,277	07/15/97	Zhang et al	437	21	11/02/94
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	JP 7-135318	05/23/95	Semiconductor Energy Laboratory Co., Ltd.			11/05/93
	JP 9-312260	12/02/97	Semiconductor Energy Laboratory Co., Ltd.			11/29/96
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	JP 11-191628	07/13/99	Semiconductor Energy Laboratory Co., Ltd.			05/16/98
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	<p>Yoshida, T. et al, "A Full-Color Thresholdless Antiferroelectric LCD Exhibiting Wide Viewing Angle with Fast Response Time," <i>SID 97 Digest</i>, pp. 841-844, 1997.</p> <p>Furue, H. et al, "Characteristics and Driving Scheme of Polymer-Stabilized Monostable FLCD Exhibiting Fast Response Time and High Contrast Ratio with Gray-Scale Capability," <i>SID 98 Digest</i>, pp. 782-785, 1998.</p> <p>Hatano, M. et al, "A Novel Self-Aligned Gate-Overlapped LDD Poly-Si TFT with High Reliability and Performance," <i>IEDM Technical Digest 97</i>, pp. 523-526, 1997.</p> <p>English abstract re Japanese patent application no. 7-130652, published May 19, 1995.</p> <p>English abstract re Japanese patent application no. 7-135318 published May 23, 1995.</p> <p>English abstract re Japanese patent application no. 9-312260 published December 2, 1997.</p> <p>English abstract re Japanese patent application no. 10-247735, published September 14, 1998.</p> <p>English abstract re Japanese patent application no. 10-294280, published November 4, 1998.</p> <p>English abstract re Japanese patent application no. 11-191628, published July 13, 1999.</p> <p>English abstract re Japanese patent application no. 11-345767, published December 14, 1999.</p> <p>English abstract re Japanese patent application no. 11-354442, published December 24, 1999.</p>
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	<u>Applicant</u> Hisashi OHTANI et al	
	<u>Filing Date</u> March 28, 2000	<u>Group</u> 1180- 2611

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V	5,372,971	12/13/94	Kang et al	437	195	10/01/92
V	5,468,342	11/21/95	Nulty et al	156	643-1	04/28/94
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